

### REMARKS

Claims 1-12 are presented for consideration, with Claim 1 being independent.

Editorial changes have been made to independent Claim 1 and selected dependent claims.

Applicant is submitting concurrently herewith a Substitute Specification pursuant to 37 C.F.R. §1.125(b). A marked-up version of the Substitute Specification showing all the changes to the specification is also enclosed. The Substitute Specification contains no new matter. In amending the specification, the suggested changes as set forth on page 2 of the Office Action have been incorporated.

The drawings were objected to for containing a reference number (110) not discussed in the specification. In response to this objection, the specification has been amended to include a discussion of support unit 110 (see page 11, line 4). Accordingly, reconsideration and withdrawal of the objection to the drawings is respectfully requested.

Claims 1-12 stand rejected under 35 U.S.C. §102(b) as allegedly being anticipated by Takahashi '093. This rejection is respectfully traversed.

Applicant's invention as set forth in Claim 1 relates to an exposure apparatus for sequentially performing exposure of device patterns provided in a pattern effective area of a photo-mask onto shot areas of a wafer. The apparatus includes an illumination unit for collectively illuminating the entire pattern effective area of the photo-mask contained within an illumination range with exposure light, a mask stage that moves the photo-mask for the illumination range in the mask scanning direction, and a wafer stage that moves the wafer in a projection range in which the pattern effective area of the photo-mask is projected in the wafer scanning direction. In addition, control means, after containing at least one shot area of the wafer

within the projection range to get device patterns provided in the pattern effective area of the photo-mask onto the one shot area of the wafer, synchronizes and controls the movements of the mask stage and the wafer stage while keeping the entire pattern effective area of the photo-mask contained within the illumination range.

In accordance with Applicant's claimed invention, an efficient and high performance exposure apparatus can be provided.

Takahashi relates to an exposure apparatus that includes an illumination unit, a mask stage 44 and a wafer stage 42. A controller 43 controls sequential movement of the mask stage and the wafer stage. In contrast to Applicant's claimed invention, however, Takashi does not teach or suggest, inter alia, illuminating the entire pattern effective area of the photo-mask contained within an illumination range with exposure light and, after containing at least one shot area of the wafer within the projection range to get device patterns provided in the pattern effective area of the photo-mask onto the one shot area of the wafer, synchronizing and controlling the movement of the mask stage and the wafer stage while keeping the entire pattern effective area of the photo-mask contained within the illumination range. Instead, Takahashi shows in Figure 3 a shot area  $x_0-x_n$  on the wafer and a smaller illumination area W. With this arrangement, the mask stage must be scanned by the controller 43 in a step and scan exposure method (generally of the type discussed in the Background of the Invention section of the subject specification).

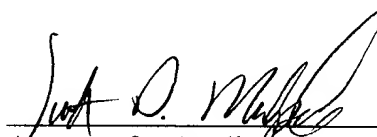
Accordingly, it is respectfully submitted that Takahashi fails to anticipate or render obvious Applicant's claimed invention, and thus reconsideration and withdrawal of the rejection under 35 U.S.C. §102 is respectfully requested.

Thus, it is submitted that Applicant's invention as set forth in independent Claim 1 is patentable over the cited art. In addition, dependent Claims 2-12 set forth additional features of Applicant's invention. Independent consideration of the dependent claims is respectfully requested.

In view of the foregoing, reconsideration and allowance of this application is deemed to be in order and such action is respectfully requested.

Applicant's undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,



Attorney for Applicant

Scott D. Malpede

Registration No. 32,533

FITZPATRICK, CELLA, HARPER & SCINTO  
30 Rockefeller Plaza  
New York, New York 10112-3801  
Facsimile: (212) 218-2200

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